Appl. No. 10/650,504 Amdt. Dated June 30, 2008 Reply to Office Action of April 30, 2008

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1-12. (Canceled)
- (Currently amended): A method for producing a solar cell, comprising: placing a substrate for a solar cell on an electrode inside a chamber;

covering said substrate with a plate, wherein said plate is provided with a number of opening portions; and

forming textures on a surface of the substrate by using residues generated during etching and being chiefly composed of components of the substrate as an etching mask, wherein a distance between said substrate and a surface of said plate opposing said substrate in a peripheral portion of said plate is set shorter than a distance between said substrate and said surface opposing said substrate in a central portion of said plate; and then

removing the residues on the surface of the substrate.

14. (Previously presented): The method for producing a solar cell according to claim 13, wherein said textures are formed by a reactive ion etching method.

15-19. (Canceled.)

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> (Currently amended): A method for producing a solar cell, comprising: placing a substrate for a solar cell on an electrode inside a chamber;

covering said substrate with a plate provided with a number of opening portions;

forming textures on a surface of said substrate using residues generated during etching and being chiefly composed of components of the substrate as an etching mask,

wherein said plate is provided with a protruding wall on a surface opposing said substrate and said protruding wall is separated from a nearest surface of said substrate by a space; and then

removing the residues on the surface of the substrate.

21. (Previously presented): The method for producing a solar cell according to claim 20, wherein said textures are formed by a reactive ion etching method.

22-23. (Canceled.)

24. (Currently amended): The <u>A</u> method for producing a solar cell according to Claim 18, comprising:

placing a substrate for a solar cell on an electrode inside a chamber;

covering said substrate with a plate, wherein said plate is provided with a number of opening portions, and said plate is provided with a protruding wall on a surface thereof opposing said substrate; and

forming textures on a surface of the substrate by using residues generated during etching and being chiefly composed of components of the substrate as an etching mask, wherein a distance between said substrate and a surface of said plate opposing said substrate in a peripheral portion of said plate is set shorter than a

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distance between said substrate and said surface opposing said substrate in a central portion of said plate.

and said protruding wall is separated from a nearest surface thereof opposing said substrate and said protruding wall is separated from a nearest surface of said substrate by a space.

- 25. (Previously presented): The method for producing a solar cell according to Claim 20, wherein a lower end portion of said protruding wall abuts on said electrode.
- 26. (Previously presented): The method for producing a solar cell according to Claim 20, wherein the substrate for a solar cell is a silicon substrate.